

FORM PTO-1449 (REV. 7.80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 91-C-127C1	SERIAL NO. 09/803,715
OIA LIST OF REFERENCES CITED BY APPLICANT (use several sheets if necessary)		APPLICANT Jai Li	
		FILING DATE March 9, 2001	GROUP 2823

PATENT  
TRADEMARK OFFICE  
JUN 28 2001

## U. S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (if appropriate)
	AA	4,829,019	05/09/1989	Mitchell, et al.	437	069	05/12/1987

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
T-D	AB	0123384	31.10.84	EPO	—	—		
	AC	59-65445	13.4.1984	Japan	—	—	X	
	AD	0050634	12.04.1980	Japan	—	—	X	
	AE	0271956	09.11.1988	Japan	—	—	X	
	AF	0189208	30.07.1986	EPO	—	—		
	AG	0275508	27.07.1988	EPO	—	—		
	AH	0208935	21.01.1987	EPO	—	—		
	AI	WO 83/02197	23.06.1987	PCT	—	—		
T-D	AJ	0401174	05.12.1990	EPO	—	—		

## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

T-D	AK	"Silicon Processing for the VLSI Era," Vol. 2, : Process Integration by Stanley Wolf, Ph.D., 1990, pp. 38-41.
T-D	AL	International Electron Devices Meeting, Dec. 1982, Washington, D.C., "Electrical Properties of MOS Devices Made with Silo Technology," J. Hui, T.Y. Chiu, S. Wong and W.G. Oldham, IEEE, pp. 220-223.
T-D	AM	International Electron Devices Meeting, Dec. 8, 1980, Washington, D.C., "Selective Polysilicon Oxidation Technology for Defect Free Isolation," Junichi Matsanaga, Naohiro Matsukawa, Hirosi Nozawa, and Susumu Kohyama, IEEE, pp. 565-568.
T-D	AN	"Under Field Oxidation Dopant Enhancement (UFDE) for CMOS and BiCMOS Technology," Extended Abstracts of the 22nd (1990) International Conference on Solid State Devices and Materials, 1990, pp. 649-652.

EXAMINER	T-Dong	DATE CONSIDERED	5/29/03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line if not in conformance and not considered. Include copy of this form with next communication to applicant.